Cleaning system study with mounting activated species of solution using atmospheric pressure plasma

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A up-to-date semiconductor and display manufacturing process must require technology to reduce defective product recently. but cleaning process used chemical solution is comprising very harmful substance for the human body and environment. Throughout the world, many studies have been conducting with the trend by restricting in the environment in all the fields including Cleaning due to the pollution.

The aim of research is more removal efficiency and environment-friendly than existing method to remove minute particle when manufacturing semiconductor, display and something else by reducing chemical solutions, ultrapure water and gas. Our experiment uses atmospheric pressure plasma and cleaning solutions utilizing gas-liquid hybrid system at the same time. It has been increasing for activated species to mount a effectivity using electron and ion which plasma reactor of self-production generate and analysis utilizing Ozone analyzer, OES(Optical Emission Spectroscopy), DMP solution, UV/VIS spectroscopy.